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Bang-Ching Ho et al.

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[illegible]

FOREIGN PATENT DOCUMENTS

[illegible]

OTHER DOCUMENTS (Including Author, Title, Date, Portion or Pages, Etc.)

Dr -	Ding et al. "Optimization of Bottom Antireflective Coating Materials for Dual Damascene Process", <u>SPIE Proceedings</u> , 3999, (2000), pp. 910 - 918.
Th -	Pollentier et al., "Dual Damascene Back-End Patterning Using 248 nm and 193 nm Lithography", <u>Interface 2000</u> , pp. 265 - 283.

ΔΙΔΑΓΜΕΝΑ

DATA CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

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[illegible][illegible]

D	-	Gadson et al., "Top Surface Imaging Improves Copper Process Resolution", <u>Solid State Technology</u> pp. 1-5, 77(2001).

3/2006

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